

AR-N 4340 – run sheet

Allresist

nanyte.com/photoresists/ar-n-4340 · last updated 2026-07-26

Thickness: 1.4–2 μm

Softbake: 90 °C · 60 s · hotplate

Exposure dose: 140 mJ/cm²

Post-exposure bake: 95 °C · 2 min

Develop: Developer AR 300-475 · Time 60 s · Rinse DI-H₂O, 30 s ·
Method puddle